1 12 miyakawa.iin. and plasma		1		1	
2	L Number	Hits	Search Text	DB	Time stamp
2	1	. 12	miyakawa.in. and plasma		2004/09/28 12:34
Cold/198.25.ccls.) and ((atmospheric high) SPAT; SPAT; Cold/198.25.ccls.) and ((atmospheric high) SPAT; Cold/198.25.ccls.)	2	42	miyakawa.in. and plasma	D.	2004/09/28 12:40
With pressure with cluster)				US-PGPUB	
1	6	5		1	2004/09/28 12:44
and (((118/719) or (145/7345.31) or (156/345.31) or (156/345.32) or (141/9391).CCLS.) and ((anneal53 heat\$a) with silylation with curs*) - 0 (((138/719) or (156/345.31) or (156/345.31) or (156/345.32) or (141/9391).CCLS.) and ((anneal53 heat\$a) same silylation same (156/345.32) or (141/9391).CCLS.) and ((anneal53 heat\$a) same silylation same (156/345.32) or (141/9391).CCLS.) and ((anneal53 heat\$a) same silylation same (156/345.31) or (156/345.32) or (141/9391).CCLS.) and ((anneal53 heat\$a) same silicon same (156/345.32) or (141/9391).CCLS.) and ((anneal53 heat\$a) same silicon same (156/345.32) or (141/9391).CCLS.) and ((anneal53 heat\$a) same silicon same (156/345.32) or (141/9391).CCLS.) and ((anneal53 heat\$a) same silicon same (156/345.32) or (141/9391).CCLS.) and ((anneal53 heat\$a) same silicon same (156/345.32) or (141/9391).CCLS.) and ((anneal53 heat\$a) same silicon same (156/345.32) or (141/9391).CCLS.) and ((anneal53 heat\$a) same silicon same (156/345.32) or (141/9391).CCLS.) and ((anneal53 heat\$a) same silicon same (156/345.32) or (141/9391).CCLS.) and ((anneal53 heat\$a) same silicon same (156/345.32) or (141/9391).CCLS.) and ((anneal53 heat\$a) same silicon same (156/345.32) or (141/9391).CCLS.) and ((anneal53 heat\$a) same (156/345.32) or (141/9391).CCLS.) and ((anneal53 heat\$a) same (156/345.32) or (411/9391).CCLS.) and (anneal53 heat\$a) same (156/345.32) or (411/9391).CCLS.) and (anneal53 heat\$a) same (156/345.32) or (411/9391).CCLS.) and (anneal53 heat\$a) same (156/345.31) or (156/345.32) or (411/9391).CCLS.) and (anneal53 heat\$a) same (156/345.31) or (156/345.		63			
1166/345.32) or (414/939).CCIS.} 0 ((118/719) or (156/345.31) or (156/345.31) or (156/345.31) or (156/345.32) or (414/939)).CCIS.} and (4nneal33 haet4s) with silylation with curs3) 0 ((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCIS.] and (118/719) or (156/345.31) or (156/345.32) or (414/939)).CCIS.] 059AT; 03-PGPUB 059AT; 03-PGPU	'	63		1	2004/09/28 12:45
0 ((((1187/19) or ((1419/39)).CCLS.) and ((anneal53 heat\$) with silylation with curs3)				US-PGPUB	
(156/345.32) or (414/939)).CCLS.) and (1018/719) or (156/345.31) or (156/345.31) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) and (1018/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) and (118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) 3534 atmospher\$3 with pressure with plasma or (414/939) or (414/939)).CCLS. (118/719) or (156/345.31) or (156/345.32) or (144/939)).CCLS.) 50 (atmospher\$3 with pressure with plasma) and ((118/719) or (156/345.31) or (156/345.31) or (156/345.31) or (156/345.31) or (156/345.32) or (144/939)).CCLS.) 6 557813.0.URN. USPAT (156/345.31) or (156/345.31) o	_	0		USPAT:	2003/05/13 11:25
Cur\$3 0 ((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) and ((anneal\$3 heat\$s) same silylation same cur\$3)				1	
0					
(156/345,32) or (414/939)).CCLS.) and ((anneal\$3 heat\$s) same silylation same cur\$3)					
Curs	_	0		1	2003/05/13 11:32
Cur\$3 Cur\$3 Cur\$3 SpAT; USPAT; US				05-FGF0B	
- 09/502,126					
3534 atmospher\$3 with pressure with plasma USPAT;	-	1	09/502,126	USPAT;	2003/05/13 11:23
1709				1	
1709 ((118/719) or (156/345.31) or (156/345.32) USPAT; US-PGPUB USPAT; US-PG	-	3534	atmospher\$3 with pressure with plasma		2003/05/13 11:26
or (414/939).CCLS. (atmosphers) with pressure with plasma) and ((118/719) or (156/345.31) or (156/345.32) or (414/939).CCLS.) (156/345.32) or (414/939).CCLS.) (166/345.32) or (414/939).CCLS.) and (168/345.31) or (166/345.32) or (414/939).CCLS.) and (25 metals) and (35	_	1700	((118/719) or (156/3/5 31) or (156/3/5 32)	1	2003/05/12 12-24
So	,	1,09			2003/03/13 12:34
Company Comp	– .	50	(atmospher\$3 with pressure with plasma)	1	2004/09/28 12:44
- 6 5578130.URPN. USPAT USPAT (156/345.31) or (156/345.32) or (414/939).CCIS.) and (166/345.32) or (414/939).CCIS.) and (166/345.32) or (414/939).CCIS.) and (166/345.32) or (414/939).CCIS.) and (186/345.31) or (156/345.32) or (414/939).CCIS.) or (156/345.31) or (156/345.32) or (414/939).CCIS.) or (156/345.31) or (156/345.31) or (156/345.32) or (414/939).CCIS.) or (414/939).CC				US-PGPUB	
3		_			
(156/345.32) or (414/939)).CCLS.) and ((anneal\$3 heat\$\$) same silicon same cur\$3] (cur\$3 with chamber) and (anneal\$3 with chamber) and ((silicon silylation) with USPAT; chamber) and ((silicon silylation) with USPAT; chamber) and ((silicon silylation) with USPAT; coly3/05/13 12:17 (chamber) and ((silicon silylation) with USPAT; coly3/05/13 12:17 (chamber) and ((silicon silylation) with USPAT; coly3/05/13 12:17 (chamber) and (silicon silylation) with USPAT; coly3/05/13 12:17 (chamber) and (silicon silylation) with USPAT; coly3/05/13 12:17 (chamber) and (silicon silylation) with chamber uspar; coly3/05/13 12:39 (cur\$3/14/2) (spin with coating with uniform\$3 (cur\$3/15/4) (spin with coating with uniform\$3 (cur\$3/15/15/4) (spin with coating with uniform\$3/15/15/4) (spin with coating with uniform\$3/15/15/15/15/15/15/15/15/15/15/15/15/15/	1 -			1	
((anneal83 heat\$s) same silicon same cur\$3) (cur\$3 with chamber) and (anneal\$3 with chamber) and ((silicon silylation) with chamber) (cur\$3 with chamber) and ((silicon silylation) with chamber) 8 ("4944895" "5047369" "5858457" "595857" "6218302" "6284682").PN. 1 "6218302" "6284682").PN. 1 "APCVD" and (((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) 17 "APCVD" with plasma and (((118/719) or (156/345.31) or (156/345.32) or (156/345.32) or (156/345.32) or (156/345.32) or (166/345.32) or (166/345.31) or (156/345.32) or (166/345.33) or (156/345.32) or (166/345.33) or (156/345.33) or (156/		,			2003/05/13 11:34
Cur\$3 with chamber and (anneal\$3 with chamber) and (silicon silylation) with chamber chamber and ((silicon silylation) with chamber chamber and ((silicon silylation) with chamber with with chamber with with chamber with with chamber with with with with with with with with			((anneal\$3 heat\$s) same silicon same	00 10100	
chamber) and ((silicon silylation) with chamber) ("4944895" "5047369" "5858457" USPAT			cur\$3)		
Chamber S	-	49		•	2003/05/13 12:17
Section Sect				US-PGPUB	
"5958577" "6048804" "6153511" "6218302" "6284682").PN. "high pressure deposition module" "APCVD" 1374 "APCVD" "APCVD" and (((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) "APCVD" with plasma "APCVD" with plasma ond (((118/719) or (156/345.32) or (156/345.31) or (156/345.32) or (156/345.32	_	ρ ,		HCDAM	2002/05/12 11.57
"6218302" "6284682").PN. USPAT; US-PGPUB USPAT; US				USPAI	2003/03/13 11:57
S-PGPUB					,
- 1374 "APCVD" USPAT; US-PGPUB	-	1	"high pressure deposition module"	USPAT;	2003/05/13 12:33
- 17 "APCVD" and (((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) - 464 "APCVD" with plasma USPAT; US-PGPUB U		1274	Wa David II	1	
- 17 "APCVD" and (((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) - 464 "APCVD" with plasma USPAT; US-PGPUB U	_	13/4	"APCVD"		2003/05/13 12:39
Company Comp	_	17	"APCVD" and (((118/719) or (156/345.31) or		2003/05/13 12-34
- 464 "APCVD" with plasma ("APCVD" with plasma) and (((118/719) or (156/345.31) or (156/345.32) or (141/939)).CCLS.) 9 "silylation chamber" - 44 silylation with chamber 5 (silylation with chamber) not "silylation chamber" ("6451118").PN. 5 (spin with coating with uniform\$3 (((118/719) or (156/345.31) or (156/345.32) or (156/3		′			
1 ("APCVD" with plasma) and (((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) 9	-	464			2003/05/13 12:42
(156/345.31) or (156/345.32) or (414/939)).CCLS.) 9		-	(HADOVIDH and About 12		000040-41-
(414/939)).CCLS.) "silylation chamber" USPAT; US-PGPUB U	-	1	("APOVD" With plasma) and (((118/719) or		2003/05/13 12:39
9 "silylation chamber" 44 silylation with chamber 35 (silylation with chamber) not "silylation chamber" ("6451118").PN. 1667 spin with coating with uniform\$3 ((1187719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) spin with coating with uniform\$3 with atmoshperic with deposit\$3 spin with coating with uniform\$3 same (atmoshperic with deposit\$3) spin with coating with uniform\$3 and (118/\$.ccls.) (spin with coating with uniform\$3 with unifo		1		US-FGFUB,	
- 44 silylation with chamber 35 (silylation with chamber) not "silylation USPAT; US-PGPUB (((118/719) or (156/345.31) or ((156/345.32) or (414/939)).CCLS.) - 0 spin with coating with uniform\$3 with uspat; us-PGPUB uspin with coating with uniform\$3 with uspat; us-PGPUB uspin with coating with uniform\$3 same (atmoshperic with deposit\$3) us-PGPUB uspat; us		9		USPAT:	2003/05/13 12:44
35			-	I -	
35	_	44	silylation with chamber		2003/05/13 12:44
- 1 ("6451118").PN. US-PGPUB USPAT; 2003/05/13 13:05 - 1667 spin with coating with uniform\$3 USPAT; 2003/05/13 15:34 - 5 (spin with coating with uniform\$3) and USPAT; 2003/05/13 15:37 - (((118/719) or (156/345.31) or US-PGPUB (156/345.32) or (414/939)).CCLS.) - 0 spin with coating with uniform\$3 with atmoshperic with deposit\$3 - 0 spin with coating with uniform\$3 same (USPAT; 2003/05/13 15:35 US-PGPUB (USPAT; 2003/05/13 15:36 US-PGPUB (USPAT; 2003/05/13 15:36 US-PGPUB (Spin with coating with uniform\$3 same (USPAT; 2003/05/13 15:36 US-PGPUB (Spin with coating with uniform\$3 and (USPAT; 2003/05/13 15:40 USPAT; 2003/05/1	_	25	(gilulation with showban) and Wadara	1	2002/05/22 22 55
1 ("6451118").PN. 1667 spin with coating with uniform\$3 (spin with coating with uniform\$3) and (((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) 10 spin with coating with uniform\$3 with atmoshperic with deposit\$3 10 spin with coating with uniform\$3 same (18 atmoshperic with deposit\$3) 162 (spin with coating with uniform\$3) and (118/\$.ccls.) 163 (spin with coating with uniform\$3) and (118/\$.ccls.) 164 (spin with coating with uniform\$3 with uniform\$3 with uniform\$3 with uniform\$3 and (118/\$.ccls.) 165 (spin with coating with uniform\$3) and (118/\$.ccls.) 1667 US-PGPUB USPAT; (2003/05/13 15:35 US-PGPUB USPAT; (2003/05/13 15:36 US-PGPUB USPAT; (2003/05/13 15:40 US-PGPUB		35			2003/05/13 13:05
- 1667 spin with coating with uniform\$3	-	1			2003/05/13 13:05
Spin with coating with uniform\$3 and (((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.)					111,10,10
Spin with coating with uniform\$3 and (((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.)		1667	spin with coating with uniform\$3	USPAT;	2003/05/13 15:34
(((118/719) or (156/345.31) or (156/345.32) or (414/939)).CCLS.) spin with coating with uniform\$\$3 with atmoshperic with deposit\$\$3 spin with coating with uniform\$\$3 same (USPAT; 2003/05/13 15:35 atmoshperic with deposit\$\$3 spin with coating with uniform\$\$3 same (USPAT; 2003/05/13 15:36 atmoshperic with deposit\$\$3) (spin with coating with uniform\$\$3 and (USPAT; 2003/05/13 15:40 (118/\$.ccls.)) (spin with coating with uniform\$\$3 with atmospheric) and (118/\$.ccls.) ypar; 2003/05/13 15:40 (USPAT; 2003/05/13 15:40	_	_	Vanin with marking the site Act		
162 (156/345.32) or (414/939)).CCLS.) atmoshperic with deposit\$3 spin with coating with uniform\$3 same (5		· ·	2003/05/13 15:37
- 0 spin with coating with uniform\$3 with USPAT; US-PGPUB Plasma with (atmospheric high) with EPO; JPO; 2003/11/18 11:15				OS-EGEOR	
atmoshperic with deposit\$3 spin with coating with uniform\$3 same (-	0		USPAT;	2003/05/13 15:35
atmoshperic with deposit\$3) (spin with coating with uniform\$3) and USPAT; 2003/05/13 15:40 (118/\$.ccls.) (spin with coating with uniform\$3 with USPAT; 2003/05/13 15:40 (spin with coating with uniform\$3 with atmospheric) and (118/\$.ccls.) plasma with (atmospheric high) with EPO; JPO; 2003/11/18 11:15			atmoshperic with deposit\$3		
- 162 (spin with coating with uniform\$3) and USPAT; 2003/05/13 15:40 US-PGPUB USPAT; US-PGPUB USPAT; 2003/05/13 15:40 USPAT; 2003/05/13 US	-	0			2003/05/13 15:36
- \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \	_	162			2002/05/12 15 10
- 4 (spin with coating with uniform\$3 with USPAT; 2003/05/13 15:40 us-pgpuB ush plasma with (atmospheric high) with EPO; JPO; 2003/11/18 11:15		102		· ·	2003/05/13 15:40
atmospheric) and (118/\$.ccls.) plasma with (atmospheric high) with US-PGPUB EPO; JPO; 2003/11/18 11:15	_	4			2003/05/13 15:40
- 3584 plasma with (atmospheric high) with EPO; JPO; 2003/11/18 11:15		.	atmospheric) and (118/\$.ccls.)		,,
pressure DERWENT	-	3584		EPO; JPO;	2003/11/18 11:15
			pressure	DERWENT	

		`				
			1257	<pre>plasma with (atmospheric high) with pressure with (coat\$3 deposit\$3 layer film)</pre>	EPO; JPO; DERWENT	2003/11/18 11:29
	-		380	(plasma with (atmospheric high) with pressure with (coat\$3 deposit\$3 layer	EPO; JPO; DERWENT	2003/11/18 11:30
	_		135	film)) and c23c016\$.ipc. (plasma with (atmospheric) with pressure with (coat\$3 deposit\$3 layer film)) and	EPO; JPO; DERWENT	2003/11/18 12:17
	-		30	with (coat\$3 deposit\$3 layer film) with (semiconductor dielectric)) and	EPO; JPO; DERWENT	2003/11/18 11:20
	-		3232	c23c016\$.ipc. plasma with (atmospheric high) with pressure with (coat\$3 deposit\$3 layer	USPAT; US-PGPUB	2003/11/18 11:29
	-		20	film) (plasma with (atmospheric high) with pressure with (coat\$3 deposit\$3 layer film) and 118 (coat\$	EPO; JPO; DERWENT	2003/11/18 12:59
	-		330	film)) and 118/\$.ccls. (plasma with (atmospheric high) with pressure with (coat\$3 deposit\$3 layer film)) and 118/\$.ccls.	USPAT; US-PGPUB	2003/11/18 12:59
			2	(plasma with (atmospheric high) with pressure with (coat\$3 deposit\$3 layer film)) and 414/\$.ccls.	USPAT; US-PGPUB	2003/11/18 11:31
	-		135	(plasma with (atmospheric high) with pressure with (coat\$3 deposit\$3 layer film)) and 156/345.\$.ccls.	USPAT; US-PGPUB	2003/11/18 11:31
	-		41	(plasma with (atmospheric high) with pressure with (coat\$3 deposit\$3 layer film)) and 118/719.ccls.	USPAT; US-PGPUB	2003/11/18 11:31
	_		33	("5319247").PN. 5319247.URPN.	USPAT; US-PGPUB	2003/11/18 11:53
	-		1154	"atmospheric pressure" with plasma with (deposit\$3 coat\$3 film layer)	USPAT USPAT; US-PGPUB	2003/11/18 11:45 2003/11/18 11:54
	_		376	"atmospheric pressure" with plasma with (deposit\$3 coat\$3 film layer) ("atmospheric pressure" with plasma with	EPO; JPO; DERWENT EPO; JPO;	2003/11/18 11:54 2003/11/18 11:54
	_		215	<pre>(deposit\$3 coat\$3 film layer)) same semiconductor ("atmospheric pressure" with plasma with (deposit\$3 coat\$3 film layer)) same</pre>	DERWENT USPAT; US-PGPUB	2003/11/18 11:59
	-		330	semiconductor (plasma with (atmospheric high) with pressure with (coat\$3 deposit\$3 layer	USPAT; US-PGPUB	2003/11/18 12:17
	-		2	film)) and 118/\$.ccls. (in\$1line same cluster) and c23c016\$.ipc.	EPO; JPO; DERWENT	2003/11/18 12:18
	_		9 24	(in\$1line same cluster) and 118/719.ccls.	USPAT; US-PGPUB	2003/11/18 12:18
	-		18	(plasma with "atmospheric pressure") and 118/719.ccls. 5651867.URPN.	USPAT; US-PGPUB USPAT	2003/11/18 13:53
	_		1	("6342275").PN. "18249"	USPAT; US-PGPUB	2003/11/18 14:56
	-		. 669	miyakawa.in.	EPO; JPO; DERWENT EPO; JPO;	2003/11/18 14:56
	_		10	miyakawa.in. and plasma	DERWENT EPO; JPO;	2004/09/28 12:34
	-		26	barnes-michael.in. cox-michael-s\$.in. lai-canfeng.in. parks-joun.in.	DERWENT EPO; JPO;	2003/11/18 15:02
			58	barnes-michael.in. cox-michael-s\$.in. lai-canfeng.in. parks-joun.in.	DERWENT USPAT; US-PGPUB	2003/11/18 15:02
	- -		10	"electromagnetic wave marker" "electromagnetic wave marker"	EPO; JPO; DERWENT	2003/11/18 16:48
	_		. 0	"electromagnetic wave marker" "electromagnetic wave" with lane\$1marker	USPAT; US-PGPUB USPAT;	2003/11/18 16:49
Ĺ					US-PGPUB	2000, 11, 10 10.45

ر. آ	_	27	"electromagnetic wave" with lane	USPAT; US-PGPUB	2003/11/18 16:50
-	-	9	plasma and ((atmospheric ambient high) with pressure with cluster)	EPO; JPO; DERWENT	2004/06/08 15:53
-	_	22		EPO; JPO; DERWENT	2004/06/08 15:53
-	_	3747	plasma and ((atmospheric ambient high) with pressure) and cluster	USPAT; US-PGPUB	2004/06/08 15:53
-	-	847	(plasma same ((atmospheric ambient high) with pressure)) and cluster	USPAT; US-PGPUB	2004/06/08 15:54
-	-	36		USPAT; US-PGPUB	2004/06/08 16:23
-	-	14	"4523897" "4640667" "4718836"	USPAT	2004/06/08 16:03
	_		"5009575" "5165864" "5238362" "5672322" "5803713" "5820354" "5871336" "6179573").PN.		
-		0 0	6736606.URPN. "apcvd" same cluster same plasma	USPAT USPAT; US-PGPUB	2004/06/08 16:12 2004/06/08 16:24
-	-	0	"apcvd" same cluster same plasma	EPO; JPO; DERWENT	2004/06/08 16:24
-	-	14	"apcvd" same plasma	EPO; JPO; DERWENT	2004/06/08 16:25
-	-	. 825	"apcvd" same plasma ,	USPAT; US-PGPUB	2004/06/08 16:25
- -	•	7	<pre>"apcvd" same plasma same ((cluster)((multiple plural\$3 several) with (chamber apparatus units)))</pre>	USPAT; US-PGPUB	2004/06/08 16:31
-		728676	("apcvd" same plasma) and (silicon and valley).as. ((cluster)((multiple plural\$3	USPAT; US-PGPUB	2004/06/08 16:32
-		7	several) with (chamber apparatus units))) ("apcvd" same plasma) and (silicon and valley).as.	USPAT;	2004/06/08 16:32
-	•	7	("apcvd" same plasma) and (valley).as.	US-PGPUB USPAT; US-PGPUB	2004/06/08 16:32
-		1	("6143080").PN.	USPAT; US-PGPUB	2004/06/09 13:15
-		2	(("4834020") or ("5136975")).PN.	USPAT; US-PGPUB	2004/06/09 13:15
-		10	("4834020" "5136975" "5413671" "5683516" "5776254" "5849088" "5863337" "5888579" "5976258"	USPAT	2004/06/09 13:17
-	i	. 1	"6022414").PN. ("6451118").PN.	USPAT;	2004/06/09 15:53
-	·	5.	118/718.ccls. and (spin with coat\$3)	US-PGPUB USPAT;	2004/06/09 15:05
-		42	(US-5863338-\$ or US-5626677-\$ or US-5587207-\$ or US-5578130-\$ or	US-PGPUB USPAT;	2004/06/09 15:20
			US-6559070-\$ or US-6562128-\$ or US-6338756-\$ or US-6001739-\$ or US-6451118-\$ or US-5743965-\$ or	US-PGPUB; EPO; JPO; DERWENT	
		·	US-5562772-\$ or US-5099782-\$ or US-4640846-\$ or US-5319247-\$ or US-6342275-\$ or US-6143080-\$ or		
			US-5605867-\$ or US-5484749-\$ or US-5041304-\$ or US-4003770-\$ or US-6207005-\$ or US-6627039-\$ or		,
	-		US-6736606-\$ or US-6026589-\$ or US-5776254-\$).did. or (US-20030039766-\$ or US-20020134310-\$ or US-20020197878-\$ or		
			US-20030106791-\$ or US-20030044154-\$).did. or (WO-9518249-\$).did. or (JP-2001168029-\$ or JP-2001035835-\$ or JP-08298245-\$ or		
			JP-06330326-\$ or JP-06041755-\$ or JP-01306569-\$ or JP-08203891-\$).did. or (EP-678914-\$ or DE-4135810-\$ or		
L			EP-431951-\$ or US-6342275-\$).did.		r

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-`	0	((US-5863338-\$ or US-5626677-\$ or	USPAT;	2004/06/09 15:20
		US-5587207-\$ or US-5578130-\$ or	US-PGPUB	
		US-6559070-\$ or US-6562128-\$ or	1	
		US-6338756-\$ or US-6001739-\$ or		
		US-6451118-\$ or US-5743965-\$ or		
		US-5562772-\$ or US-5099782-\$ or		
		US-4640846-\$ or US-5319247-\$ or		
		US-6342275-\$ or US-6143080-\$ or		· ·
		US-5605867-\$ or US-5484749-\$ or		
		US-5041304-\$ or US-4003770-\$ or	,	
		US-6207005-\$ or US-6627039-\$ or		
		US-6736606-\$ or US-6026589-\$ or		
		US-5776254-\$).did. or (US-20030039766-\$ or		
		US-20020134310-\$ or US-20020197878-\$ or		
		US-20030106791-\$ or US-20030044154-\$).did.		
		or (WO-9518249-\$).did. or (JP-2001168029-\$		
		or JP-2001035835-\$ or JP-08298245-\$ or		
1		JP-06330326-\$ or JP-06041755-\$ or		
		JP-01306569-\$ or JP-08203891-\$).did. or		
		(EP-678914-\$ or DE-4135810-\$ or	İ	
		EP-431951-\$ or US-6342275-\$).did.) and		
		imahashi.in.		
-	2	118/719.ccls. and imahashi.in.	USPAT;	2004/06/09 15:24
			US-PGPUB	
-	10	118/719.ccls. and ((atmospheric high) with	USPAT;	2004/06/09 15:25
	-	pressure with cluster)	US-PGPUB	
-	5	(204/298.25.ccls.) and ((atmospheric high)	USPAT;	2004/09/28 12:44
		with pressure with cluster)	US-PGPUB	
_	1	("6143080").PN.	USPAT;	2004/06/09 16:00
			US-PGPUB	
_	2	(("5683516") or ("5849088")).PN.	USPAT;	2004/06/09 16:00
			US-PGPUB	